

- 1 1. A method comprising:
2 forming a photoresist by attaching a photoactive
3 compound to a polymer backbone.
- 1 2. The method of claim 1 including attaching
2 diazonaphthoquinone as the photoactive compound.
- 1 3. The method of claim 2 including attaching
2 hydroxystyrene groups to said backbone.
- 1 4. The method of claim 3 including attaching a first
2 moiety to one hydroxystyrene group and a second moiety,
3 different from said first moiety, to a second
4 hydroxystyrene group.
- 1 5. The method of claim 4 including selecting said
2 moieties from hydrogen, hydroxyl, and alkyl.
- 1 6. The method of claim 1 including using from 10 to
2 20% of diazonaphthoquinone on a molar basis.
- 1 7. The method of claim 2 including forming non-
2 reactive compounds upon exposure to radiation.
- 1 8. The method of claim 4 including forming nitrogen
2 upon irradiation.

1 9. A photoresist comprising:
2 a polymer backbone; and
3 a photoactive compound attached to said backbone.

1 10. The photoresist of claim 9 wherein said
2 photoactive compound includes diazonaphthoquinone.

1 11. The photoresist of claim 9 including
2 hydroxystyrene attached to said backbone.

1 12. The photoresist of claim 11 including two
2 hydroxystyrene groups attached to said backbone, each of
3 said hydroxystyrene groups having a moiety attached to said
4 group, the moiety attached to one hydroxystyrene group
5 being different than the moiety attached to the other
6 hydroxystyrene group.

1 13. The photoresist of claim 12 wherein said moieties
2 are selected from hydrogen, hydroxyl, and alkyl.

1 14. The photoresist of claim 10 wherein
2 diazonaphthoquinone is from 10 to 20% on a molar basis.

1 15. A method comprising:
2 attaching diazonaphthoquinone to a polymer
3 backbone; and
4 attaching at least two hydroxystyrene groups to
5 each backbone to form a photoresist.

1 16. The method of claim 15 including attaching a
2 first moiety to one hydroxystyrene group and a second
3 moiety, different from said first moiety, to a second
4 hydroxystyrene group.

1 17. The method of claim 16 including selecting said
2 moieties from hydrogen, hydroxyl, and alkyl.

1 18. The method of claim 15 including using from 10 to
2 20% of diazonaphthoquinone on a molar basis.

1 19. The method of claim 15 including forming non-
2 reactive compounds upon exposure to radiation.

1 20. The method of claim 19 including forming nitrogen
2 upon irradiation.